

<b>Notice of References Cited</b>	Application/Control No. 10/736,386		Applicant(s)/Patent Under Reexamination WHITEFIELD ET AL.	
	Examiner Hugh Jones		Art Unit 2128	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2005/0039089	02-2005	Gedamu et al.	714/718
*	B	US-2008/0021677	01-2008	Buxton et al.	702/184
*	C	US-6,847,855	01-2005	Poeppel, Gerhard	700/110
*	D	US-6,070,004	05-2000	Prein, Frank	716/10
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Abercrombie et al. (inventors). Method for Calculating High-Resolution Wafer Parameter Profiles; 2004 IEEE/SEMI Advanced Semiconductor Manufacturing Conference, pp. 119-123.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.